Amendments to the Specification and Abstract

Please amend the specification to read as follows.

Page 1, between lines 2 and 3, at the left margin, insert the heading: Technical Field;

between lines 8 and 9, at the left margin, insert the heading: Background.

Page 4, between lines 22 and 23, at the left margin, insert the heading: Description of the Invention.

Pages 5 and 6, the paragraph bridging pages 5 and 6, from line 21 on page 5 to line 3 on page 6, should be amended as follows:

The ~~magnet~~ magnetic field pattern further comprises an unbalanced long-range field pattern which is asymmetrical and is generated by increasing magnetic flux along the outer area relative to magnetic flux along the inner area, whereby the long range field reaches the substrate surface with a component of magnetic field parallel to the substrate surface of at least 0.1 Gauss. In the magnetic field pattern there is generated a plasma discharge and the substrate surface is plasma treated, whereby the asymmetrically unbalanced field pattern is swept along the substrate surface.

Page 14, between lines 18 and 19, insert the following heading, at the left margin, and brief descriptions of Figs. 1 and 2:

Brief Description of Drawings

Fig 1 schematically shows the generation of a magnetron field pattern F_m and, additionally, of an unbalanced field pattern F_u in relation to a first inner magnet subarrangement and a second outer magnet subarrangement and target;

Fig. 2 schematically shows the generation of a magnetron field pattern Fm and, additionally, of an asymmetrically unbalanced field pattern F_{AU} in relation to a first, inner magnet subarrangement and a second, outer magnet subarrangement of a magnetron according to the present invention;

Page 16, between lines 14 and 15, at the left margin, insert the heading:

Detailed Description of Embodiments.

Pages 26 and 27, the paragraph from line 27 on page 26 to line 10 on page 27 should be amended to read as follows:

Moreover with predetermined ~~fix~~ fixed electrical supply power to the magnetron source and predetermined ~~fix~~ fixed pressure in the magnetron chamber pulsating of the magnetron supply and thus of the magnetron discharge helps to ionize the metal with increased degree. From Fig. 11 where the metal ionization ratio is shown in dependency of the percentage amount of off-time at the pulsating electric magnetron source supply it becomes evident that with increasing off-time percentage the metal ionization increases. At a duty cycle with 50 % off-times of the pulsating electrical magnetron source supply Fig. 10 reveals a preferred optimum frequency range between 100 and 200 kHz for optimum metal ionization.